

NuSolv XTR100P Positive Photoresist Stripper

A drop-in replacement for Baker PRS-3000 stripper

Is a 100% chemical equivalent to Baker PRS-3000 from JT Baker[®].

PRODUCT DESCRIPTION: NuSolv XTR 100P photoresist stripper and ash/etch residue remover provides versatile cleaning in traditional semiconductor with aluminum silicon dioxide layers; compound semiconductor and packaging applications (flip chips/bumps). NuSolv XTR100P is Semicon grade and meets electronics grade specs.

CHARACTERISTICS:

- Efficient bulk resists removal providing photoresist removal in 5–20 minutes
- 100% water soluble formulation—no intermediate solvent rinse required resulting in decreased total process time and costs
- Designed to provide broad process latitude in terms of processing time and temperature
- Long bath life—typically greater than 24 hours
- Does not contain fluoride or hydroxylamine

DIRECTIONS FOR USE:

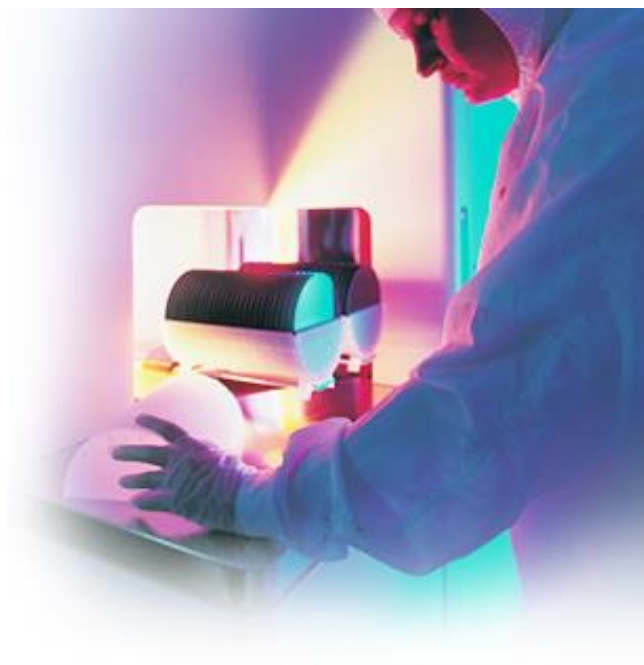
1. Bath or Batch Spray 65° to 85° C 5-20 min
2. DI Rinse
3. Dry

COMPATIBLE MATERIALS:

- Stainless Steel
- Glass
- Quartz
- PTFE
- Polypropylene
- PFA

PHYSICAL PROPERTIES:

	NuSolv XTR 100P
Flash Point – open cup	103°C
Flash Point – closed cup	93°C
pH, @ 5% bv	11.5
Bath Life	>24 hours
Freezing Point	-30°C
Boiling Point	165°C
Solubility in water	Complete
Viscosity (@22°C)	5-9 cps
Surface Tension	41 dyne/cm
Specific Gravity	1.07 kg/L



Availability: 5-gallon and 55-gallon containers; 300 gallon tote-bins and bulk tankers.

Shipment: Freight classification is “cleaning compound, NOBIN – Liquid.”

Storage: Keep out of direct sunlight. Keep from freezing. Store between 40-120°F.

Disposal: Dispose of in accordance with local, state, and federal regulations. For assistance with disposal contact NuGeneration Technologies at 888-99-NuGen or email: info@nugentec.com.